

用于CEPC内层顶点探测器的高计数率CMOS像素探测器 芯片研制

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On behalf of the CEPC MOST2 Vertex detector design team

第三届半导体辐射探测器研讨会

5月11-14日，2023

内容概要

- 项目背景
- TaichuPix 芯片概述
- TaichuPix 芯片设计与测试
- 总结与展望

CEPC 顶点探测器需求

Circular Electron Positron Collider (CEPC) proposed as a Higgs factory.

■ Efficient tagging of heavy quarks (b/c) and τ leptons

→ Impact parameter resolution,

$$\sigma_{r\phi} = 5 \oplus \frac{10}{(p \cdot \sin^{3/2} \theta)} (\mu m)$$

Physics driven requirements

$\sigma_{s.p.}$ **2.8 μm**

Material budget **0.15% X_0 /layer**

r of Inner most layer **16 mm**

Running constraints

Air cooling

beam-related background

radiation damage

Sensor specifications

Small pixel **~16 μm**

Thinning to **50 μm**

low power **50 mW/cm²**

fast readout **~1 μs**

radiation tolerance

≤ 3.4 Mrad/ year

$\leq 6.2 \times 10^{12} n_{eq}/(cm^2 \text{ year})$

Baseline design parameters for CEPC vertex detector

	R (mm)	$ z $ (mm)	$ \cos \theta $	σ (μm)
Layer 1	16	62.5	0.97	2.8
Layer 2	18	62.5	0.96	6
Layer 3	37	125.0	0.96	4
Layer 4	39	125.0	0.95	4
Layer 5	58	125.0	0.91	4
Layer 6	60	125.0	0.90	4

Ref: CEPC Conceptual Design Report, Volume II - Physics & Detector, <http://cepc.ihep.ac.cn/>

TaichuPix 芯片研发背景

Silicon Vertex Detector **Prototype** – MOST (2018–2023)

Sensor technology CMOS TowerJazz

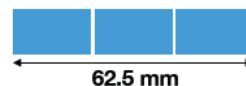
- ✦ Design sensor with large area and high resolution
- ✦ Integration of front-end electronic on sensor chip

Benefit from MOST 1 research program

Ref: Introduction to the Pixel MOST2 Project, Joao Costa, 2018.6

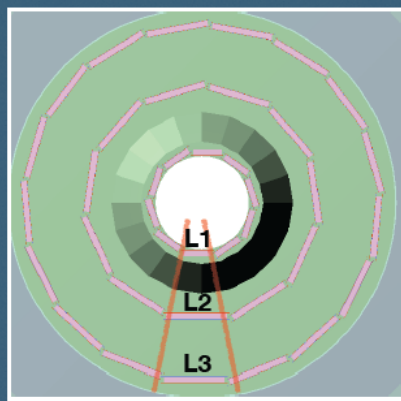
Double sided ladder

Layer 1 (11 mm x 62.5 mm)
Chip size: 11 mm X 20.8 mm



3 X 2 layer = 6 chips

3-layer sector



Baseline MOST2 goal:
3-layer prototype

Default layout requires different size ladders

Keep it simple for baseline design

L1

L2

L3

3-layers
same size
same chip

Goals:

1 MRad TID
3-5 μ m SP resolution

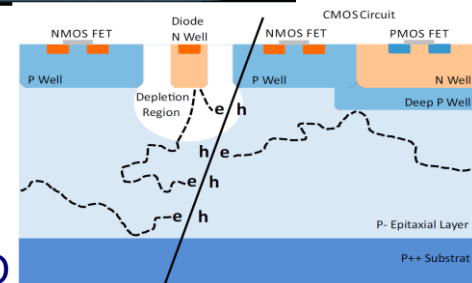
Integrate electronics
readout

Design and produce
light and rigid
support structures

8

■ Motivation for **TaichuPix** chip design

- Large-scale & full functionality pixel chip
- Fit to be assembled on ladders with backend Elec. & DAQ



CMOS pixel sensor

TaichuPix 芯片设计指标

■ Bunch spacing

- Higgs: 680 ns; W: 210 ns; Z: **25 ns**
- Max. bunch rate: 40 M/s

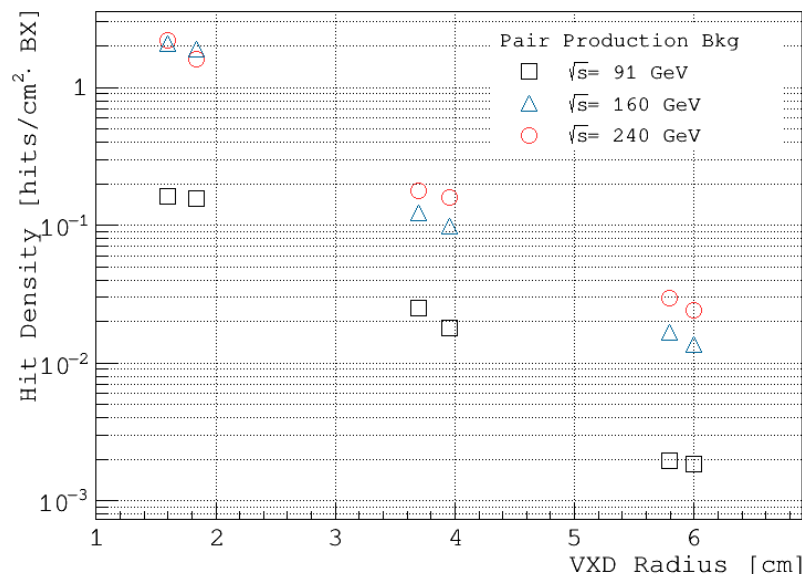
■ Hit density

- 2.5 hits/bunch/cm² for Higgs/W; 0.2 hits/bunch/cm² for Z

■ Cluster size: ~3 pixels/hit

- Epi-layer thickness: ~18 μm
- Pixel size: 25 μm $\times$ 25 μm

Hit Density vs. VXD Radius



Ref: CEPC Conceptual Design Report, Volume II

For Vertex	Specs	For High rate Vertex	Specs.	For Ladder Prototype	Specs.
Pixel pitch	$\leq 25 \mu\text{m}$	Hit rate	120 MHz/chip	Pixel array	512 row $\times$ 1024 col
TID	$>1 \text{ Mrad}$	Date rate	3.84 Gbps --triggerless ~110 Mbps --trigger	Power Density	$< 200 \text{ mW/cm}^2$ (air cooling)
		Dead time	$< 500 \text{ ns}$ (for 98% efficiency)	Chip size	$\sim 1.4 \text{ cm} \times 2.56 \text{ cm}$

TaichuPix 芯片结构

Motivation: a large-scale & full functionality pixel sensor for the first 6-layer vertex detector prototype

■ Pixel $25\ \mu\text{m} \times 25\ \mu\text{m}$

- Continuously active front-end, in-pixel discrimination
- Fast-readout digital, with masking & testing config. logic

■ Column-drain readout for pixel matrix

- Priority based data-driven readout
- **Time stamp added at EOC**
- **Readout time: 50 ns** for each pixel

■ 2-level FIFO architecture

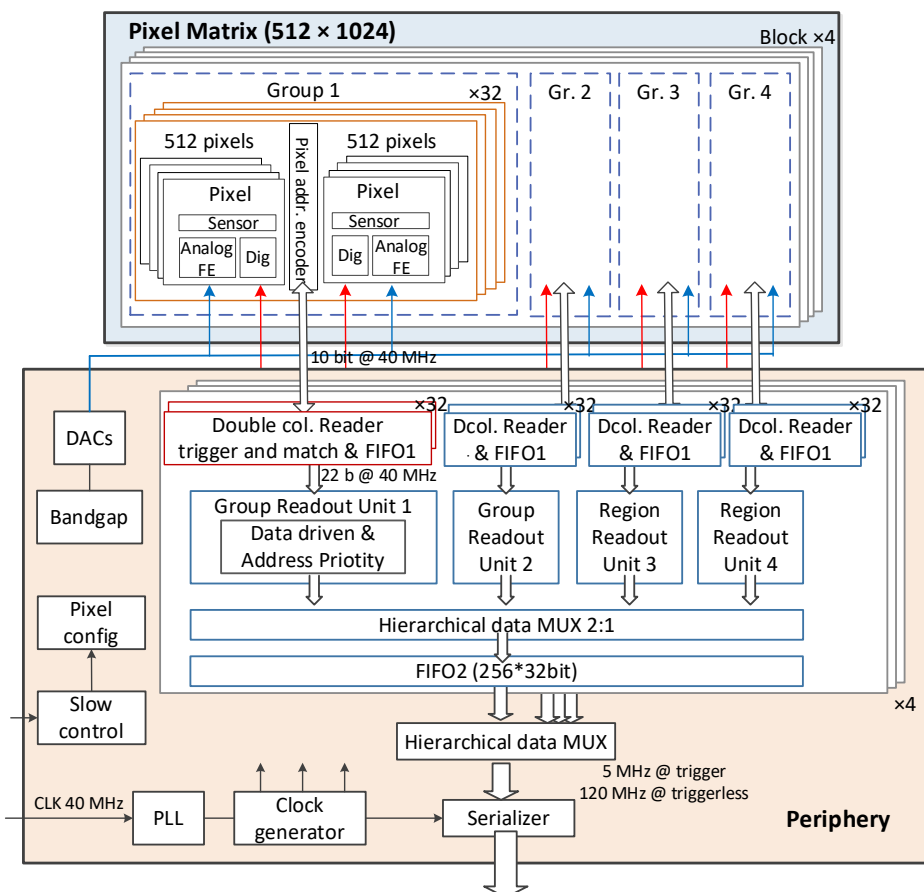
- L1 FIFO: de-randomize the injecting charge
- L2 FIFO: match the in/out data rate between core and interface

■ Trigger-less & Trigger mode compatible

- Trigger-less: 3.84 Gbps data interface
- Trigger: data coincidence by time stamp, only matched event will be readout

■ Features standalone operation

- On-chip bias generation, LDO, slow control, etc.



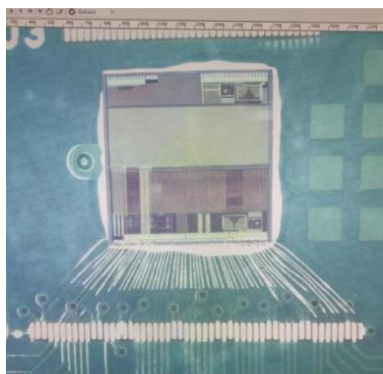
TaichuPix 原型芯片概述

■ Major challenges for the CMOS sensor

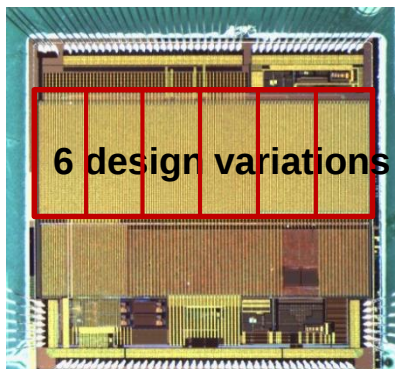
- Small pixel size → high resolution (3-5 μm)
- High readout speed (dead time < 500 ns @ 40 MHz) → for CEPC Z pole
- Radiation tolerance (per year): 1 Mrad TID

■ Completed 3 round of sensor prototyping in 180 nm CMOS process

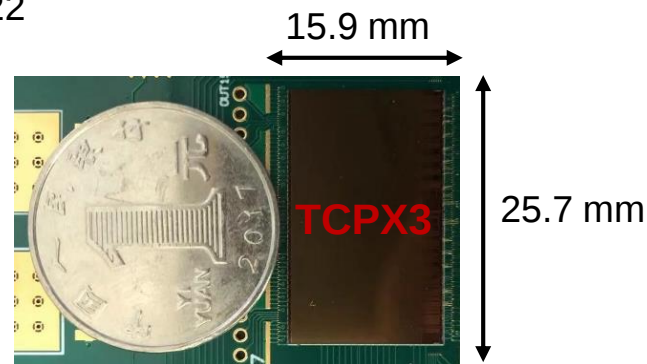
- Two MPW chips (5 mm $\times$ 5 mm)
 - TaichuPix-1: 2019.06 – 2019.11
 - TaichuPix-2: 2020.02 – 2020.06
- 1st engineering run
 - Full-scale chip: TaichuPix-3, received in July 2022



TaichuPix-1



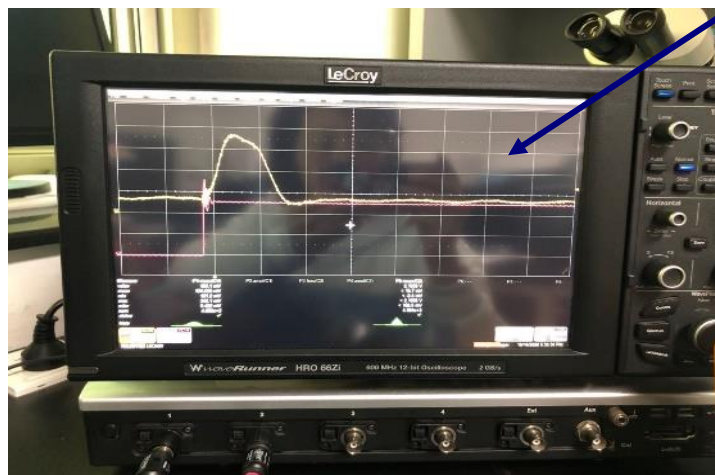
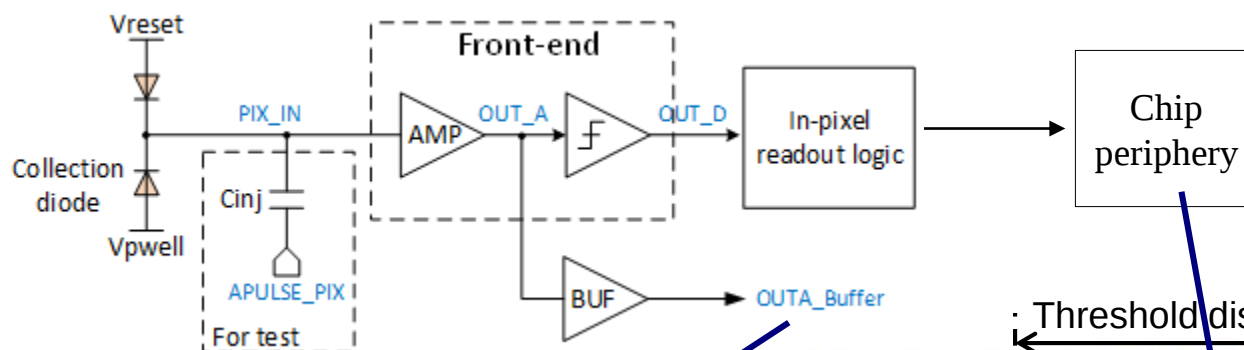
TaichuPix-2



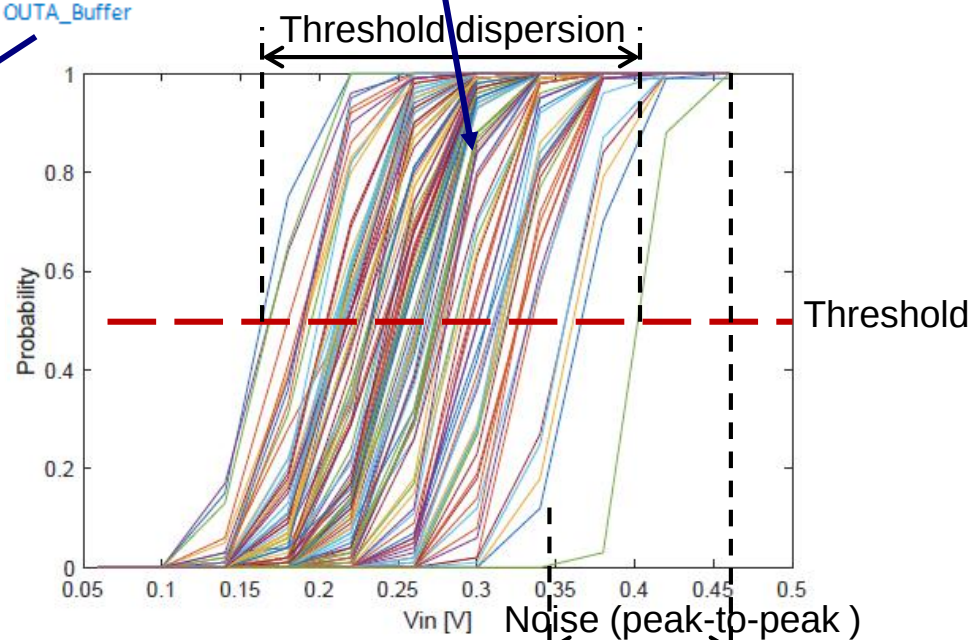
TaichuPix-3
Pixel size: 25 μm $\times$ 25 μm

Electrical test

- Electrical performance verified by injecting external voltage pulses into pixel front-end



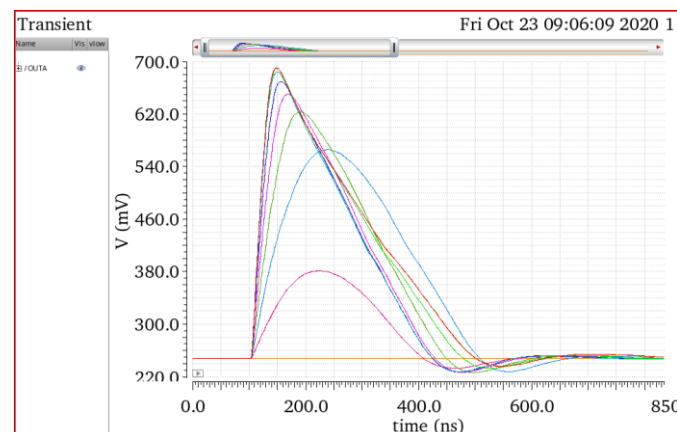
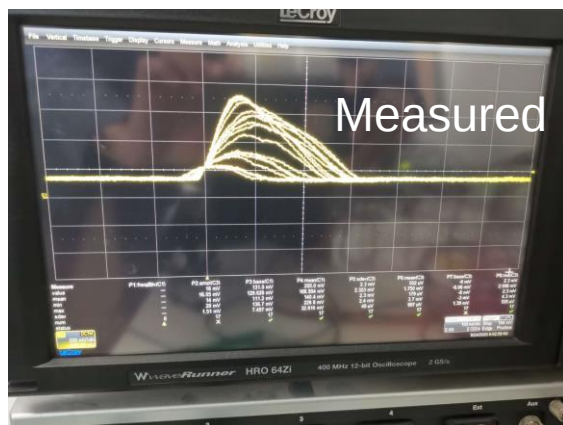
Analog output of a pixel @ $V_{in} = 0.9 \text{ V}$



Measured "S-curve" for 128 pixels

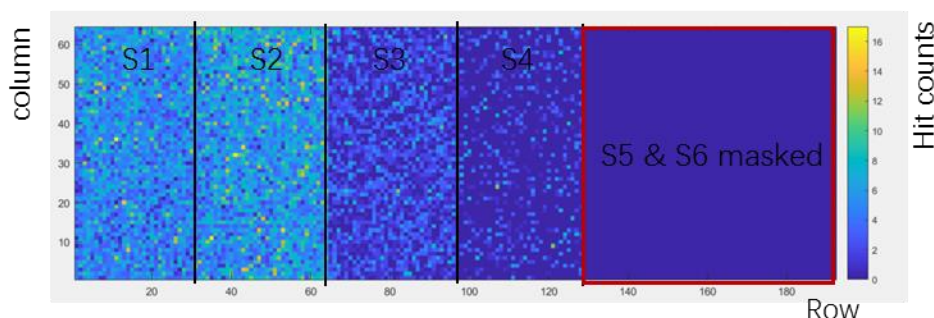
Functionality of complete signal chain of TaichuPix2

- **Functionality of the complete signal chain** (including sensor, analog front-end, in-pixel logic readout, matrix periphery readout and data transmission unit) was firstly **proved** with an X-ray source and a laser source.

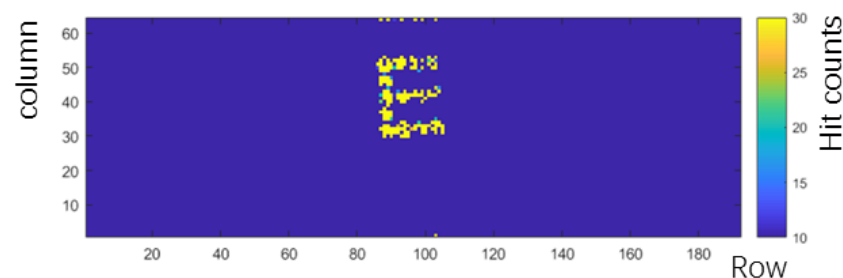


TaichuPix2 response to **X-ray** tube (cutting energy @ 6keV)

Simulated analog output with different input signal



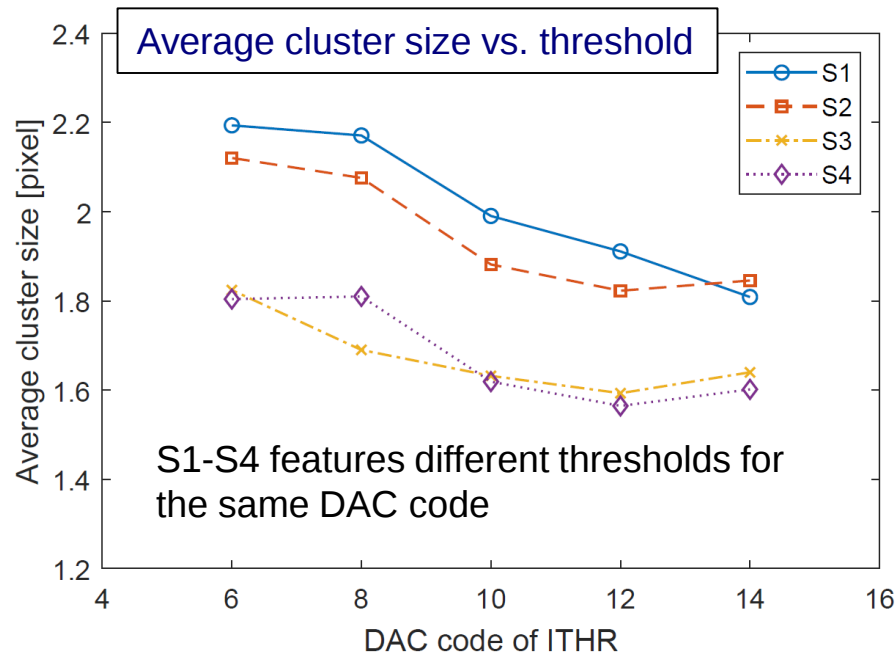
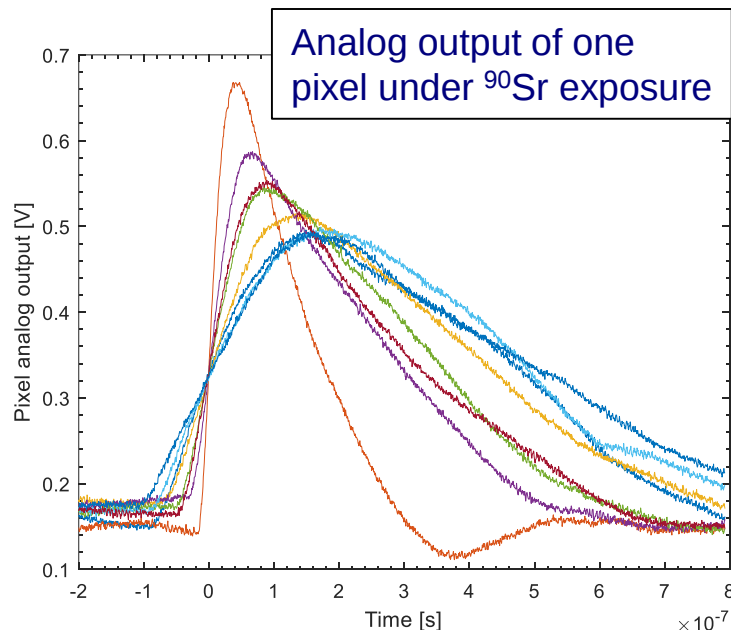
Hit map of the TaichuPix-2 under X-ray from the X-tube voltage of 8 kV for 5 min.



Letter imaging obtained with a 1064 nm laser spot scanning on the TaichuPix-2

TaichuPix2 test with ^{90}Sr

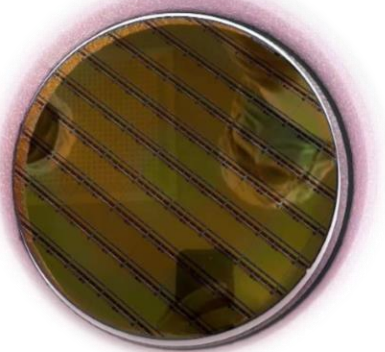
■ TC2 exposure to ^{90}Sr source at different threshold setting (ITHR)



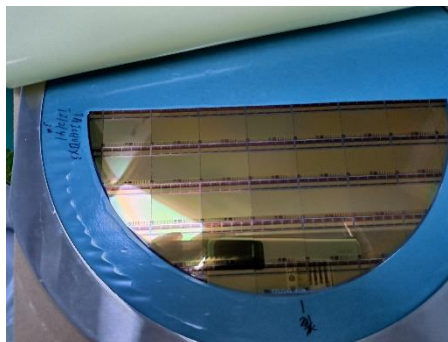
- Shape and amplitude of analog signal as expected, but peaking time and pulse length larger than simulation.
- Average cluster size decreases with threshold as expected
- **Average cluster size for S1-S4 less than 3 as expected**
 - Indicates the estimated maximum hit rate (36 MHz/cm²) reasonable
 - Cluster size >1, benefits the spatial resolution (better than $pitch/\sqrt{12} = 7.2 \mu\text{m}$)

Large-scale sensor TaichuPix-3

- 6 TaichuPix-3 wafers arrived at IHEP in July
 - One wafer thinned down to 150 μm and diced



8-inch wafer

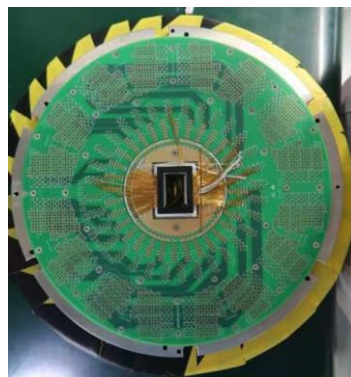


Wafer after thinning and dicing

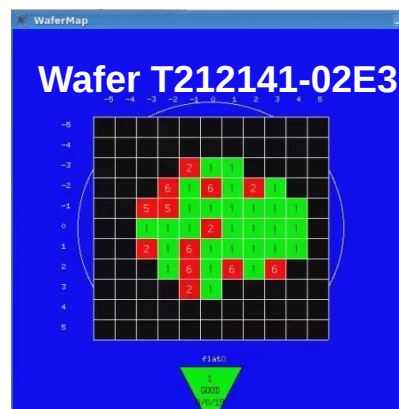


Thickness after thinning

- Complete wafer testing on probe-station $\rightarrow$ chip selecting & yield evaluation



Probe card for wafer test



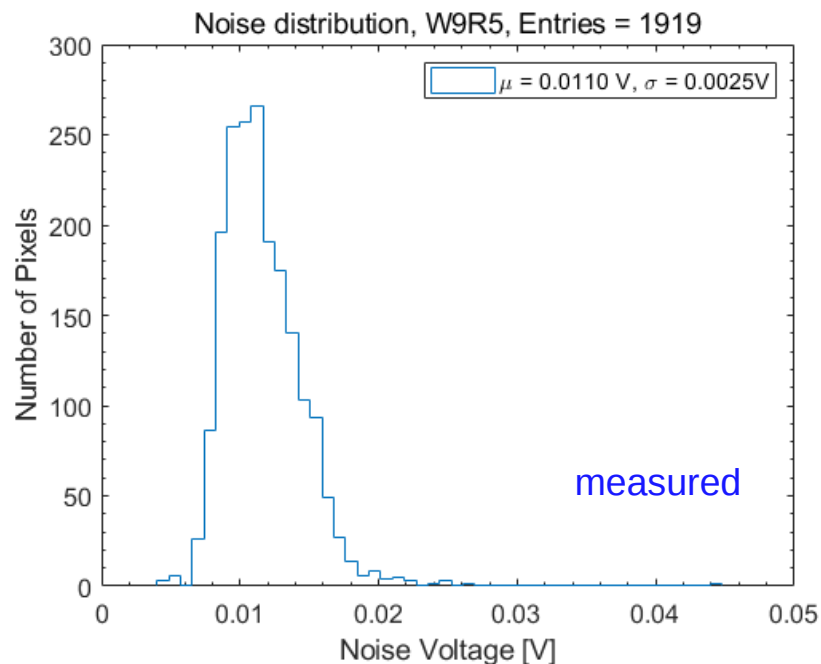
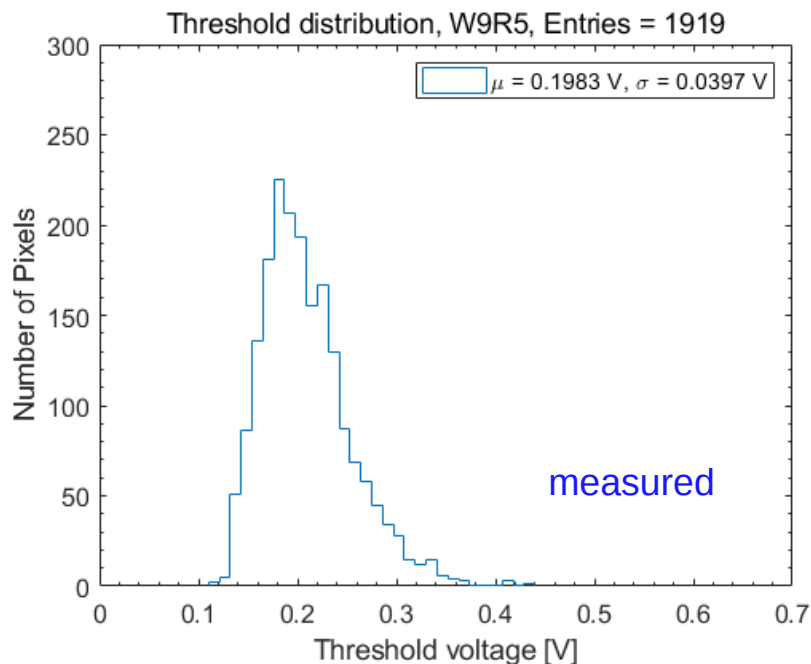
An example of wafer test result

5 wafers tested

- 2 wafer based on standard process
 - Reasonable yield achieved
- 3 wafer based on modified process
 - Preliminary result indicates lower yield than the std. process

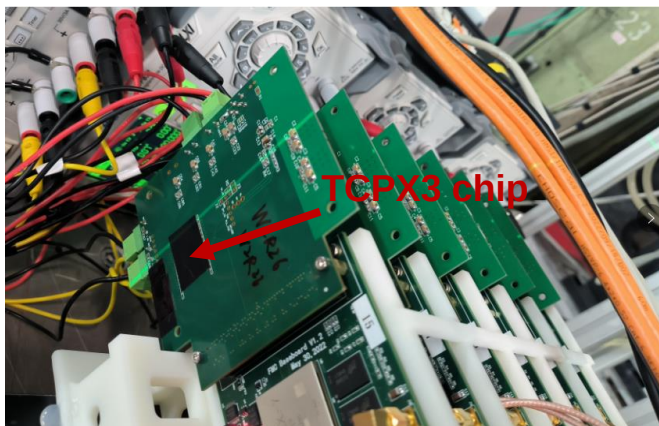
TaichuPix-3芯片像素阈值和噪声

- Pixel threshold and noise were measured with selected pixels
 - Average threshold ~ 215 e⁻, threshold dispersion ~ 43 e⁻, temporal noise ~ 12 e⁻ @ nominal bias setting



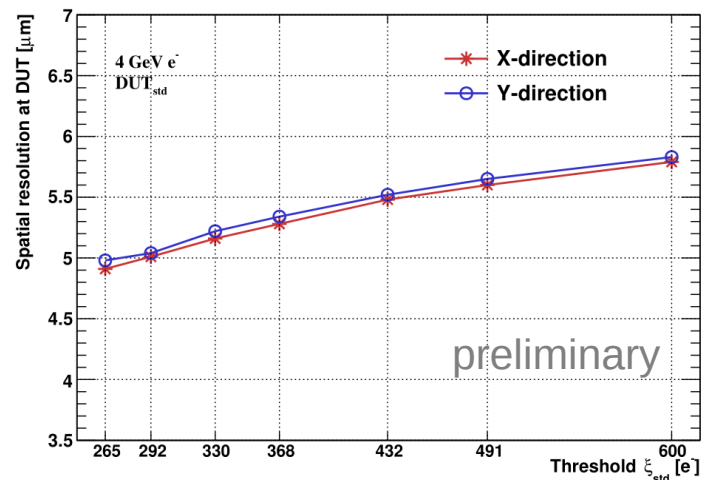
TaichuPix-3 telescope

- The 6-layer of TaichuPix-3 telescope built
 - Each layer consists of a TaichuPix-3 bonding board and a FPGA readout board

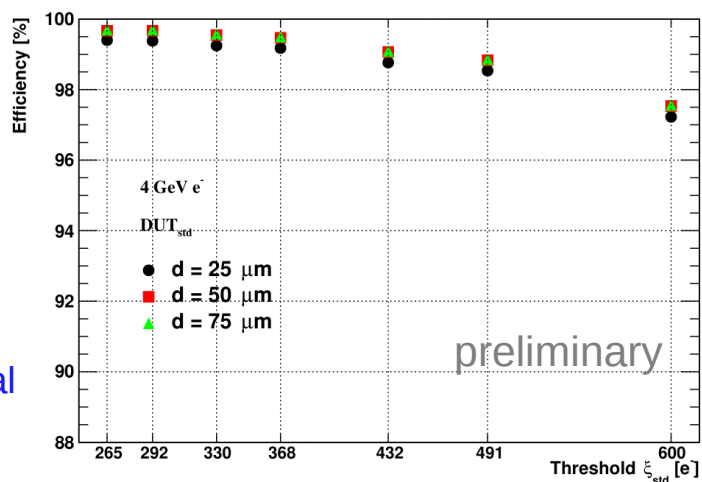


6-layer TaichuPix-3 telescope

- TaichuPix-3 telescope achieved the expected goal in the DESY testbeam
 - Basically works well during the beam test time
 - The preliminary offline results indicate the best spatial resolution could be $< 5 \mu\text{m}$



Spatial resolution vs. pixel threshold



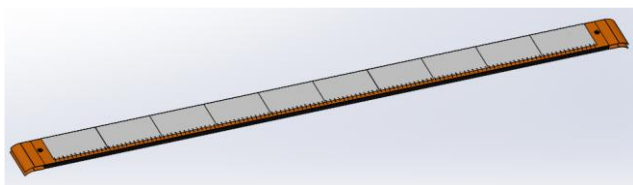
Detection efficiency vs. pixel threshold

Ladder readout

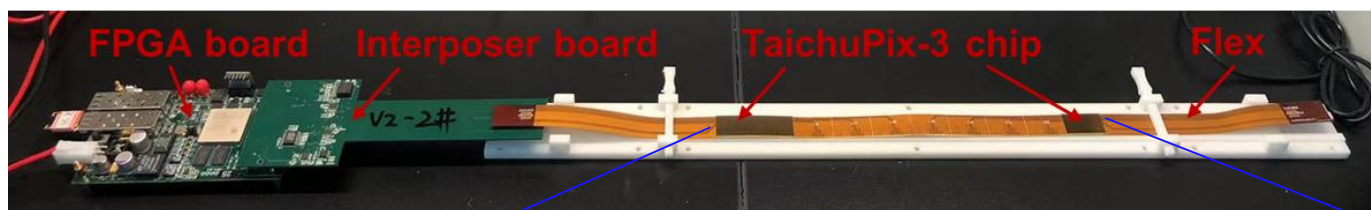
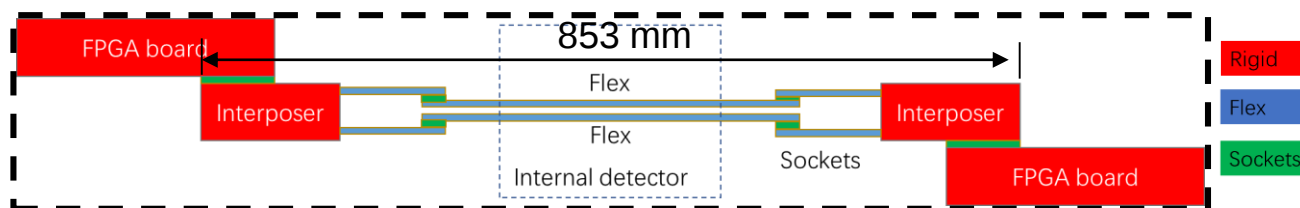
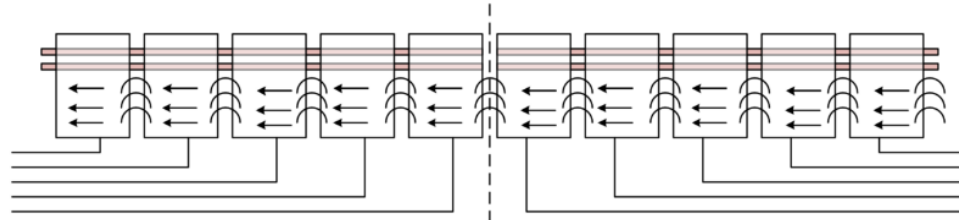
Completed detector module (ladder) design

- Detector module (ladder) = 10 sensors + readout board + support structure + control board
- Sensors will be glued and wire bonded to the flexible PCB
- Flexible PCB will be supported by carbon fiber support structure
- Signal, clock, control, power, ground will be handled by control board through flexible PCB

3D module of the ladder



Schematic of ladder readout

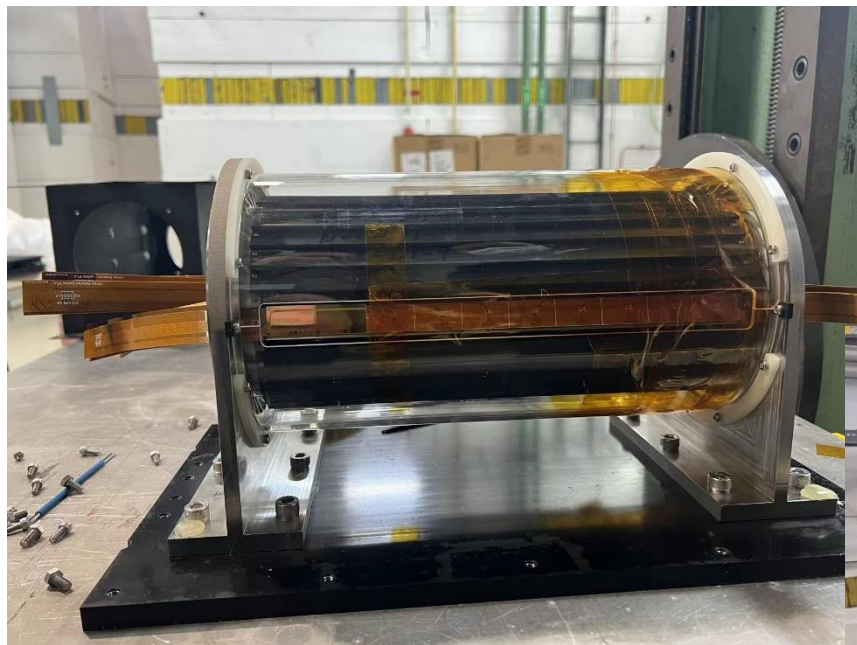


Ladder readout system

U10	U9	U8	U7	U6	U5	U4	U3	U2	U1
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Detector prototype

- **6 double-sided layers assembled on the detector prototype**
 - 12 flex boards with two TaichuPix-3 chips bonded on each flex
 - Readout boards on one side of the detector



总结与展望

- 面向CEPC顶点探测器需求，基于MOST2项目支持，开展TaichuPix芯片研发
 - 采用单片式 CMOS像素探测器技术
 - 像素尺寸 $25\ \mu\text{m} \times 25\ \mu\text{m}$, 读出时间 50 ns/pixel
 - 经过三次流片实现了全功能全尺寸 ($25.7\ \text{mm} \times 15.9\ \text{mm}$) 芯片，满足设计指标
- 基于全尺寸太初芯片初步研制了束流望远镜和探测器原型样机
 - 2022年12月对束流望远镜进行了电子束流测试
 - 2023年4月对探测器原型样机进行了电子束流测试

详细内容→ 5月13日下午吴天涯报告

- 展望
 - 进一步完成完整版探测器模块的研制和原型样机安装
 - 优化Ladder读出
 - 提高探测器系统稳定性